	MA	STER COPY KEEP		
•	'REPORT	DOCUMENTATION	AD-A25	5 240 T
•	<pre>Algorithm and an angle of the second se</pre>	ر من المراجع بين المحمولة من المراجع ا المراجع المراجع بين المراجع الم محمولة مراجع المراجع ال		
	1. AGENCY USE ONLY (Leave D	Jul 92 REPORT DATE	Final	Jun 89-31 May 92
	4. TITLE AND SUBTITLE			5. FUNDING NUMBERS
	Reliability of Sol-Gel Derived Ferroelectric Memories			DAAL03-89-K-0104
	6. AUTHOR(S)			
	Sandwip K. Dey		TIC	
	7. PERFORMING ORGANIZATION	NAME(S) AND ADDE SES	P111992	8. PERFORMING ORGANIZATION REPORT NUMBER
	Arizona State Un Tempe, AZ 85287		C	
	9. SPONSORING / MONITORING A	GENCY NAME(S) AND ADDRESS(ES)	10. SPONSORING / MONITORING
	U. S. Army Research	Office		AGENCY REPORT NUMBER
	P. O. Box 12211 Research Triangle P	ark, NC 27709-2211		ARO 26827.7-PH
		and/or findings conta d not be construed as		
6	The view, opinions author(s) and shoul position, policy, of 12a. DISTRIBUTION / AVAILABILIT	d not be construed as or decision, unless so	an official Depar designated by oth	rtment of the Army
	The view, opinions author(s) and shoul position, policy, o 12a. DISTRIBUTION / AVAILABILIT Approved for public	d not be construed as or decision, unless so Y STATEMENT : release; distribution	an official Depar designated by oth	rtment of the Army ner documentation.
32-243	The view, opinions author(s) and shoul position, policy, of 12a. DISTRIBUTION / AVAILABILIT Approved for public 13. ABSTRACT (Maximum 200 wo A process was developed to solution (0.5M) were necess wafers. An addition of 155 resulted in PZT films of ed Dielectric constant and tan were 12 and 25 µC/cm ² , resp experiments, a polarization diminish from 5.8 to 5.2 µD reduction of the switched	d not be construed as or decision, unless so y STATEMENT e release; distribution ords) prepare PZT(52/48) precurso sary to grow 0.5 µm thin fil & excess PbO aided the densi guivalent thickness in only no were 800 and 2% respection pectively. Coercive fields of n loss of 11.2% after 3.2 ye C/cm ²). High frequency nul- charge of 26% after 4x10 ¹²	an official Depar designated by oth n unlimited. or solutions. Five spin ims of polycrystalline ification process. Fi two depositions. vely, at 1 kHz. Remnan of 36-48 kV/cm were me ears was estimated (i. se fatigue data on Nb	n-on depositions of this PZT onto PT passivated silicon Ims derived from 1.5M solutions asured. From retention e., the switched charge would and Sn modified PZT showed a
	The view, opinions author(s) and shoul position, policy, of 12a. DISTRIBUTION / AVAILABILIT Approved for public 13. ABSTRACT (Maximum 200 wo A process was developed to solution (0.5M) were necess wafers. An addition of 155 resulted in PZT films of ed Dielectric constant and tan were 12 and 25 µC/cm ² , resp experiments, a polarization diminish from 5.8 to 5.2 µD reduction of the switched	d not be construed as or decision, unless so y STATEMENT e release; distribution ords) prepare PZT(52/48) precurso sary to grow 0.5 µm thin fil & excess PbO aided the densi guivalent thickness in only no were 800 and 2% respection pectively. Coercive fields of n loss of 11.2% after 3.2 ye C/cm ²). High frequency nul- charge of 26% after 4x10 ¹²	an official Depar designated by oth n unlimited. or solutions. Five spin ims of polycrystalline ification process. Fi two depositions. vely, at 1 kHz. Remnan of 36-48 kV/cm were me ears was estimated (i. se fatigue data on Nb	n-on depositions of this PZT onto PT passivated silicon Ims derived from 1.5M solutions asured. From retention e., the switched charge would and Sn modified PZT showed a
	The view, opinions author(s) and shoul position, policy, of 12a. DISTRIBUTION / AVAILABILIT Approved for public 13. ABSTRACT (Maximum 200 wo A process was developed to solution (0.5M) were necess wafers. An addition of 15% resulted in PZT films of ec Dielectric constant and tar were 12 and 25 µC/cm ² , resp experiments, a polarization diminish from 5.8 to 5.2 µC reduction of the switched of 14. SUBJECT TERMS	In the construed as or decision, unless so y STATEMENT a release; distribution () () () () () () () () () ()	an official Depar designated by oth n unlimited. or solutions. Five spin ims of polycrystalline ification process. Fi two depositions. vely, at 1 kHz. Remnan of 36-48 kV/cm were me ears was estimated (i. se fatigue data on Nb polarization reversals	n-on depositions of this PZT onto PT passivated silicon Ims derived from 1.5M solutions asured. From retention e., the switched charge would and Sn modified PZT showed a
	The view, opinions author(s) and shoul position, policy, of 12a. DISTRIBUTION / AVAILABILIT Approved for public 13. ABSTRACT (Maximum 200 wo A process was developed to solution (0.5M) were necess wafers. An addition of 15% resulted in PZT films of ec Dielectric constant and tar were 12 and 25 µC/cm ² , resp experiments, a polarization diminish from 5.8 to 5.2 µC reduction of the switched of 14. SUBJECT TERMS	d not be construed as or decision, unless so y STATEMENT e release; distribution ords) prepare PZT(52/48) precurso sary to grow 0.5 µm thin fil & excess PbO aided the densi guivalent thickness in only no were 800 and 2% respection pectively. Coercive fields of n loss of 11.2% after 3.2 ye C/cm ²). High frequency nul- charge of 26% after 4x10 ¹²	an official Depar designated by oth n unlimited. or solutions. Five spin ims of polycrystalline ification process. Fi two depositions. vely, at 1 kHz. Remnan of 36-48 kV/cm were me ears was estimated (i. se fatigue data on Nb polarization reversals	n-on depositions of this PZT onto PT passivated silicon Ims derived from 1.5M solutions asured. From retention e., the switched charge would and Sn modified PZT showed a
	The view, opinions author(s) and shoul position, policy, of 12a. DISTRIBUTION / AVAILABILIT Approved for public 13. ABSTRACT (Maximum 200 wo A process was developed to solution (0.5M) were necess wafers. An addition of 155 resulted in PZT films of ec Dielectric constant and tar were 12 and 25 µC/cm ² , resp experiments, a polarization diminish from 5.8 to 5.2 µ0 reduction of the switched of 14. SUBJECT TERMS Sol-Gel processing; fatig	d not be construed as or decision, unless so y STATEMENT e release; distribution (mds) prepare PZT(52/48) precurso sary to grow 0.5 µm thin fil & excess Pb0 aided the densi guivalent thickness in only no were 800 and 2% respection pectively. Coercive fields on n loss of 11.2% after 3.2 ym C/cm ²). High frequency nul charge of 26% after 4x10 ¹² U 4	an official Depar designated by oth n unlimited. or solutions. Five spin lms of polycrystalline ification process. Fi two depositions. vely, at 1 kHz. Remnan of 36-48 kV/cm were me ears was estimated (i. se fatigue data on Nb polarization reversals c thin films, memories	n-on depositions of this PZT onto PT passivated silicon Ims derived from 1.5M solutions asured. From retention e., the switched charge would and Sn modified PZT showed a
32-243	The view, opinions author(s) and shoul position, policy, of 12a. DISTRIBUTION / AVAILABILIT Approved for public 13. ABSTRACT (Maximum 200 wo A process was developed to solution (0.5M) were necess wafers. An addition of 15% resulted in PZT films of ec Dielectric constant and tar were 12 and 25 µC/cm ² , resp experiments, a polarization diminish from 5.8 to 5.2 µC reduction of the switched of 14. SUBJECT TERMS	In the construed as or decision, unless so y STATEMENT a release; distribution () () () () () () () () () ()	an official Depar designated by oth n unlimited. or solutions. Five spin ims of polycrystalline ification process. Fi two depositions. vely, at 1 kHz. Remnan of 36-48 kV/cm were me ears was estimated (i. se fatigue data on Nb polarization reversals	n-on depositions of this PZT onto PT passivated silicon Ims derived from 1.5M solutions asured. From retention e., the switched charge would and Sn modified PZT showed a
	The view, opinions author(s) and shoul position, policy, of 12a. DISTRIBUTION / AVAILABILIT Approved for public 13. ABSTRACT (Maximum 200 wo A process was developed to solution (0.5M) were necess wafers. An addition of 15% resulted in PZT films of ed Dielectric constant and tan were 12 and 25 µC/cm ² , resp experiments, a polarization diminish from 5.8 to 5.2 µ0 reduction of the switched of 14. SUBJECT TERMS Sol-Gel processing; fatig	d not be construed as or decision, unless so y STATEMENT e release; distribution ords) prepare PZT(52/48) precurso sary to grow 0.5 µm thin fil & excess PbO aided the densi quivalent thickness in only no were 800 and 2% respecti pectively. Coercive fields on n loss of 11.2% after 3.2 ye C/cm ²). High frequency pull charge of 26% after 4x10 ¹² f U 4	an official Depar designated by oth n unlimited. or solutions. Five spin lms of polycrystalline ification process. Fi two depositions. vely, at 1 kHz. Remnan of 36-48 kV/cm were me ears was estimated (i. se fatigue data on Nb polarization reversals c thin films, memories	n-on depositions of this PZT onto PT passivated silicor Ims derived from I.5M solutions asured. From retention e., the switched charge would and Sn modified PZT showed a

26827-PH, FR, p1/7

FINAL PROGRESS REPORT

- 1. PROPOSAL NUMBER: 26827-PH
- 2. PERIOD COVERED BY REPORT: JULY 1, 1989 TO JUNE 30, 1992
- 3. TITTLE OF PROPOSAL: RELIABILITY OF SOL-GEL DERIVED FERROELECTRIC MEMORIES
- 4. CONTRACT OR GRANT NUMBER: DAALO3-89-K-0104
- 5. NAME OF INSTITUTION: ARIZONA STATE UNIVERSITY
- 6. AUTHOR OF PROGRESS REPORT: PROFESSOR SANDWIP K. DEY
- 7. LIST OF MANUSCRIPTS SUBMITTED OR PUBLISHED UNDER ARO SPONSORSHIP DURING THIS PERIOD, INCLUDING JOURNAL REFERENCES: Please see page two of this report.
- SCIENTIFIC PERSONNEL SUPPORTED BY THIS PROJECT AND DEGREES AWARDED DURING THIS PERIOD: Mr. Anjaneya R. Modak (MS degree granted) Mr. Arup Gupta (MS degree granted) Mr. Ming-Yi Lee Mr. P. Coffman Prof. Sandwip K. Dey
- 9. REPORT OF INVENTIONS None

Sandwip K. Dey Department of Chemical, Bio and Materials Engineering Arizona State University Tempe, Arizona 85287-6006



C. .

Item 7. LIST OF MANUSCRIPTS SUBMITTED OR PUBLISHED UNDER ARO SPONSHORSHIP DURING THIS PERIOD

1) "Sol-Gel Processing and Characterization of Ferroelectric PZT Thin Films," A.R. Modak and S.K. Dey, in Ceramic Transactions, vol. 15, 477, Materials and Processes for Microelectronic Systems, eds. K.M. Nair, R. Pohanka and R.C. Buchanan, 1990.

2) "Advances in Perovskite Thin Films: Chemical Processing, Properties, and Electrical Applications," S.K. Dey, Fifth U.S.-Japan Seminar on Dielectric and Piezoelectric Ceramics, Kyoto, Japan, December 12-14, 1990.

3) "Properties of Ferroelectric PZT Thin Films From High Molarity Polymeric Precursor Solutions," A. Gupta and S.K. Dey, in <u>Ferroelectric Films</u>, Eds. A.S. Bhalla and K.M. Nair, *Ceramic Transactions*, The American Ceramic Society, **25**, 243-250 (1992).

4) "Nanostructure Evolution During the Transition of TiO₂, PbTiO₃ and PZT From Gels to Crystalline Thin Films," Z.C. Kang, A. Gupta, M.J. McKelvy, L. Eyring and S.K. Dey. *Mater. Res. Symp. Proc.*, 230, 301 (1992).

5) "Preliminary Observations on Ferroelectric $Pb(Zr_xTi_{1,x})O_3$ Thin Films With Excess Lead," S. K. Dey and A.R. Modak, sent to the Journal of the American Ceramic Society, December 1991.

6) "Transmission Electron Microscopy Observations of Sol-Gel Derived Ferroelectric PbZrO₃-PbTiO₃ Thin Films," A.R. Modak and S.K. Dey, Ferroelectrics (in press), Nov. 1991.

7) "Early Evolutionary Stages of Condensation and Crystallization in Acid and Base Catalyzed PbZrO₃-PbTiO₃ Gels: A High-Resolution Electron Microscopic Study," Z.C. Kang, S.K. Dey and L. Eyring, *Mater. Res. Symp. Proc.*, **183**, 291 (1990).

8) "The Effect of Ionizing Radiation on Sol-Gel Ferroelectric PZT Capacitors," J.M. Benedetto, R.A. Moore, F.B. McLean, P.S. Brody and S.K. Dey, *IEEE Trans. Nucl. Sci.*, NS-37[6], 1713 (1990).

BRIEF OUTLINE OF RESEARCH FINDINGS

The need for integrated ferroelectrics have led to progress in understanding of: a) organometallic precursor synthesis, b) thin film fabrication, c) evolution of the structure, and d) interfacial and radiation effects, and their influences on electrical and optical properties. Research efforts in our group, under the present ARO contract, focused on the thin film chemical processing technique of solution-gelation (sol-gel), and the electrical characterization of ferroelectric capacitor structures made thereby. In the process of such efforts, dense and crack-free ferroelectric Pb(Zr_{0.52}Ti_{0.48})O₃ or PZT (52/48) thin-films (0.5µm thick) were integrated onto Pt/Ti/SiO₂/(100)Si wafers (3 inch diameter). Dense perovskite microstructures were obtained at temperatures as low as 550°C within 15 minutes. These films exhibited remnant polarization (P_r), maximum polarization (P_{max}), and coercive field (E_c) in the range of 29-32 μ C/cm², 44-53 μ C/cm² and 50-60 kV/cm, respectively. Recent studies of high speed ferroelectric perovskite switching times <2.7ns were measured on $19x19 \,\mu\text{m}^2$ capacitors. Measurements made on 2.5x2.5 μ m² Pb(Nb,Zr,Sn,Ti)O₃ thin film capacitors gave sub-nanosecond switching times. These measurements were, however, circuit limited and were not representative of the intrinsic switching time. Interestingly, independent preliminary TEM studies on perovskite thin film samples under an applied (*in-situ*) dc-bias indicate that domain nucleation occurs at domain walls. If this result in indeed the general case, it is possible that single crystals may switch polarization more slowly than polycrystalline thin films of the same composition. Thus, future observations of intrinsic switching times (in polycrystalline films) in the 10's of picoseconds may not be surprising.

In PZT, the relaxation of internal strains through the ferroelastic effect can reorient 90° domains. This in turn, causes a retention (of the polarization) problem well below the Curie temperature. It is therefore, necessary to fabricate dense PZT films with a minimal unit cell distortion in order to improve retention performance. Figure 1 illustrates reproducible retention behavior of a 42x42 μ m² Nb-modified PZT(52/48) thin film (0.5 μ m thick) capacitor. The charge retention was characterized by measuring the polarization after a delay (since poling the capacitor into a known state) with no intervening voltage applications. The non-switching (n_s) charge remains constant while the full-switching (f_s) charge exhibits a small negative slope after 2.8 days (or 10⁵s). The difference (f_s - n_s), i.e., the retained polarization that switched (S), is 93%. Assuming that the switched charge versus delay time continues to obey this logarithmic dependence, the loss of polarization (extrapolated to 3.2 years) will be 11.2%, i.e., the retained charge will change from 5.8 to 5.15 μ C/cm². In the future, additional processes or mechanisms that limit such retention performance must be identified and controlled in integrated devices.

Early results on low frequency sinusoidal fatigue measurements on thin films indicated that compositions near the morphotropic phase boundary, i.e., PZT(52/48), are most promising. High frequency pulse fatigue measurements have demonstrated a similar trend. Figure 2 illustrates promising fatigue results of a Nb and Sn modified 42x42 μ m² PZT thin film (0.6 μ m thick) capacitor. The rise time, amplitude, pulse width, and bipolar pulse frequency of this polarization reversals study was 1ns, 4V, 33ns, and 7.1 MHz, respectively. Again, a major

challenge ahead will be to demonstrate such performances in integrated ferroelectric memory devices.

Major Achievements

The following is a compilation of major accomplishments for the three years duration of this research project.

- A process was developed to prepare PZT(52/48) precursor solution.

-Crack-free PZT(52/48) thin films were successfully deposited onto 3 inch Pt- passivated silicon wafers. Five consecutive depositions were necessary to obtain a thickness of 0.5 μ m.

- The addition of 15 mole% of excess lead (PbO) was found to densify (elimination of porosity) the thin films.

- Ferroelectric domains in 90° arrays were first observed in these films by TEM.

- A simplified process for the fabrication of ferroelectric PZT thin films, by a reduced number of deposition steps of a high molarity polymeric precursor solution was developed.

- Crack-free, dense microstructure films (0.5 μ m thick) were successfully obtained by only two depositions.

-HREM observation of the structure evolution of the final perovskite phase was made on thin films from PZT and PT precursor gels, obtained by acid and base catalyzed hydrolysis.

- The presence of acetate groups in the gel, due to the incomplete exchange of lead acetate with 2-methoxyethanol, was verified by FTIR.

- The mechanism of acetate decomposition, to the oxide, appeared to be via the carbonate intermediate, with the evolution of acetone and carbon dioxide. The acetate does not decompose completely and increases the organic content in the fired product.

- Combination of ¹H NMR and ¹³C NMR analytical techniques indicated the presence of residual acetate species in the hydrolyzed solution. The slight presence of acetates made the PZT(52/48) precursor solution more difficult to hydrolyze.

- X-ray diffraction studies showed the formation of phase pure perovskite only in a PZT(52/48) film (0.45 μ m thick), made by two deposition steps of a 1.15M precursor solution. The dielectric constant and tan δ were 800 and 2% respectively, at 1 kHz. Remnant polarization and saturation

polarization values of 12 and 25 μ C/cm² respectively, were measured, at coercive field values of 36-48 kV/cm.

- Sol-gel solid phase epitaxial growth of (110) PNZT on 3 inch diameter (0112) Sapphire was confirmed by HRTEM and x-ray analyses.

- The films were 0.6 μ m thick, transparent in the 0.5-5.6 μ m wavelength range, had a refractive index of 2.5-2.6 (at 0.6328 μ m) and an optical band gap of 3.63 eV.

26827-PH FR, p6/7





26827-PH FR, p7/7



NUMBER OF POLARIZATION REVERSALS

FIGURE 2